

# Supporting Information

## Orientation control in thin films of a high- $\chi$ block copolymer with a surface active embedded neutral layer

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**Figure S1.** F1s, N1s, and C1s XPS spectra obtained from the 20% ENL thin film at a thickness of  $1.0 L_0$  and annealing at 250 °C for 5 min after removal of 0, 1.4, 2.9, 5.7 nm of material.

